Filmetrics[®] F50 Thin-Film Mapping Analyzer

Automated Thin-Film Thickness Mapping System

Thin-film thickness of samples up to 450mm in diameter are mapped quickly and easily with the F50 advanced spectral reflectance system. The motorized r-theta stage moves automatically to selected measurement points and provides thickness measurements as fast as two points per second. The F50 has the same precision high-lifetime stage that performs millions of measurements in our production systems.

Choose one of dozens of predefined polar, rectangular, or linear map patterns, or create your own with no limit on the number of measurement points. The entire desktop system is set up in minutes and includes easyto-use, intuitive software.

Example Layers

Virtually any smooth, non-metallic film may be measured. Examples include:

SiO ₂	SiN _x	DLC	Polysilicon
Photoresist	Polymer layers	Polyimide	Amorphous Silicon

Example Applications

Semiconductor Fabrication	LCD	
Photoresist	Cell Gaps	
Oxides/Nitrides/SOI	Polyimide	
Wafer Backgrinding	ITO	
MEMS	Optical Coatings	
Photoresist	Hardness Coatings	
Silicon Membranes	Anti-Reflection Coating	



The Filmetrics Advantage

- World's leader in tabletop thin-film measurement
- 24-hour phone, e-mail, and online support
- Intuitive analysis software, standard with every system

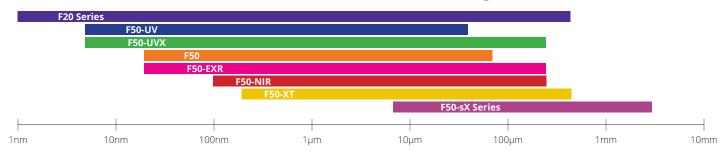
Additional Features

- Built-in online diagnostics
- Standalone analysis software included
- Sophisticated history function for saving, reproducing, and plotting results



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Thickness Measurement Range



Measurement Specifications	F50-UV	F50-UVX	F50	F50-EXR	F50-NIR	F50-XT	F50-sX
Thickness Measurement Range*	5nm-40µm	5nm-250µm	20nm-70µm	20nm-250µm	100nm-250µm	0.2µm-450µm	7µm-3mm
Min. Thickness to Measure n & k*	50nm	50nm	100nm	100nm	500nm	2µm	100µm
Wavelength Range	190-1100nm	190-1700nm	380-1050nm	380-1700nm	950-1700nm	1440-1690nm	1280-1580nm
Accuracy*: The Greater of	1nm or 0.2%	1nm or 0.2%	2nm or 0.2%	2nm or 0.2%	3nm or 0.4%	4nm or 0.4%	50nm or 0.4%
Precision	0.02nm ¹ 0.1nm ¹			1nm ¹	5nm²		
Stability	0.05nm ² 0.12nm ³			1nm ³	5nm ⁴		
Spot Size	Standard 1.5mm, Optional Down to 150µm 600µm			10µm			
Light Source Lamp MTBF	D ₂ : 2000 hours Halogen: 1200 hours Halogen: 1200 hours		200 hours		SLED: > 10 years		

General Requirements		
Power	100-240VAC, 50-60Hz, 100 Watts	
Dimensions	14W x 19D x 11H (in) 35.5W x 48.3D x 28H (cm)	
Weight	35lbs (16kg)	

Computer Requirements		
Processor Clock Speed	1.4GHz min	
Interface	USB 2.0	

Operating System	
PC⁵	Windows 10 - Latest Windows (64-bit)
МАС	OS X Catalina - Latest MAC OS Running Parallels

	200mm Chuck	300mm Chuck
Sample Size	≤ 200mm diameter	≤ 300mm diameter
Speed (Typical with Vacuum Chuck)	5 points - 5 sec. 25 points - 14 sec. 56 points - 29 sec.	5 points - 8 sec. 25 points - 21 sec. 56 points - 43 sec.

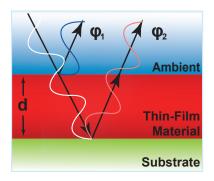
* Material dependent

- 1 1 σ of 100 measurements of 500nm SiO_2-on-Si.
- Average of 1 over 20 successive days.
- 2 1 o of 100 measurements of 100 µm SiO₂-on-Si.
- Average of 1σ over 20 successive days.
- ³ 2σ of daily average of 100 measurements of 500nm SiO₂-on-Si over 20 successive days.
- 4 2 σ of daily average of 100 measurements of 100 μm SiO_2-on-Si over 20 successive days.
- ⁵ Windows 10 Latest Windows (64-bit) and a DirectX 10 graphics card required to render 3D wafer maps



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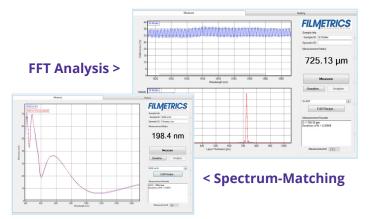
How Does It Work?



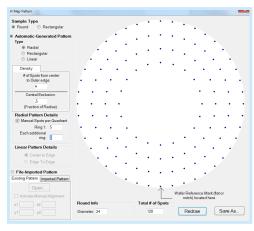
When light encounters an interface between two materials, it is partially reflected. The wave-like nature of light causes reflections from multiple interfaces (ϕ_1 , ϕ_2) to interfere with

each other, resulting in oscillations in the wavelength spectrum of the reflected light (see image above).

From the frequency of these oscillations we determine the distance between the different interfaces and thus the thickness of the materials (with more oscillations meaning greater thickness). Other material characteristics are also measured, such as refractive index and roughness. For the analysis of the spectra, our FILMeasure/ FILMapper software uses two analysis modes: Spectrum-Matching and FFT. In Spectrum-Matching mode, you can analyze thickness, as well as refractive index, whereas FFT mode is only for thickness but is often more robust for thicker films.



FILMapper Software – Measurement Automation



The Map Pattern Generator

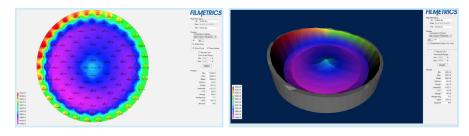
The built-in map pattern generator lets you easily generate the spot patterns needed to measure the relevant area of your samples, thus saving time during data acquisition.

Here are only some of the parameters you can adjust to customize your map's properties:

- Round or square maps
- · Radial or rectangular patterns
- Center or edge exclusion
- Spot density

Measurement Results Visualization in 2D and 3D

Whether you are measuring reflectance, film thickness, or refractive index, FILMapper lets you display the resulting measurement maps in either 2D or 3D. Switch easily between the maps for the individual measurement parameters and freely rotate 3D profiles to get an optimal view of the results.





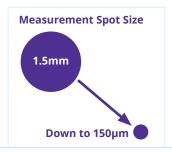
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Optional Accessories

Overcoming High Surface Roughness

For samples with a high roughness, spot sizes of 300µm or 150µm are available.

If an even smaller spot size is needed (e.g. to measure on lateral structures), take a closer look at the Filmetrics F54.



Available Chuck Sizes

Select one of our standard chuck sizes of 100mm, 200mm, 300mm, or 450mm

diameter or ask for a custommade chuck.



Staying Focused

You'll benefit from our optional autofocus if you're measuring absolute reflectance

with high accuracy or if your samples have a significant height variance. It is also important to maintain the small spot size of the sX versions.



Bigger Samples and Transmittance

With the F50-XY, measure samples as large as 590mm x 550mm and up.

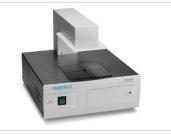
The F50-XY also allows for measurement of sample transmittance.



Looking to Do More? Extend your capabilities even further with these related products:



F3 Series for layers as thin as 1nm



F10-RT for simultaneous reflectance and transmittance



F54 Series for micro-spot measurements



Specifications subject to change without notice. 2022 KLA Corporation Rev. 05.22 Printed in the USA.